

Notice of References Cited	Application/Control No. 10/792,342	Applicant(s)/Patent Under Reexamination PRASAD, ABANESHWAR	
	Examiner Hai Vo	Art Unit 1771	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,406,363	06-2002	Xu et al.	451/296
	C	US-6,239,188	05-2001	Kihara et al.	521/159
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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